# A *Ku*-Band Oscillator Utilizing Overtone Lithium Niobate RF-MEMS Resonator for 5G

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Abstract—This letter presents a 12.9-GHz silicon germanium (SiGe) Pierce oscillator using a third antisymmetric overtone in a lithium niobate (LiNbO<sub>3</sub>) resonator for 5G communications. Quarter-wave resonators are used to satisfy the Barkhausen oscillation conditions for the third overtone while suppressing the fundamental and higher order resonances. The oscillator achieves a measured phase noise of -70 and -111 dBc/Hz at 1 and 100-kHz offsets from a 12.9-GHz carrier while consuming 20 mW of dc power. The oscillator achieves a figure-of-merit of 200 dBc/Hz at 100-kHz offset, surpassing the state-of-the-art electromagnetic (EM) and overtone MEMS oscillators. The achieved oscillation frequency is the highest reported to date for an MEMS oscillator. The demonstrated performance shows the strong potential of microwave acoustic oscillators for 5G frequency synthesis. This work will enable low-power 5G transceivers featuring high speed, high sensitivity, and high selectivity in small form factors.

Index Terms—Lithium niobate (LiNbO<sub>3</sub>), MEMS, oscillator, overtone.

#### I. Introduction

URRENTLY, the sub-3-GHz frequency bands are too congested to meet the ever-increasing data rates and communication speeds demanded by many cellular users. The call for higher bandwidths and speeds has pushed the 5G radios toward millimeter (mm)-wave frequencies such as 26–28 and 37–43.5 GHz. Apart from larger bandwidth, 5G wireless transceivers are expected to feature higher sensitivity and selectivity while producing longer battery life; all in small form factors.

To achieve all the above seamlessly, the heartbeat of the transceiver—namely, the frequency synthesizer—must be revolutionized on architecture, circuit, and device levels. Local oscillator (LO) noise directly adds to the transceiver noise figure (NF) and worsens the sensitivity while any spurs on LO considerably exacerbate the selectivity. To relax the requirements on the sensitivity and selectivity of the RF front-end for 5G, the synthesizer phase noise has to be reduced through a nonconventional way. One key challenge in implementing high-performance chip-scale synthesizers for 5G beyond 10 GHz lies in the lack of high-performance miniature resonators that can enable signal generation with minimal phase noise and power consumption.

The state-of-the-art (SoA) microwave oscillators are based on *LC* [1], microstrip [2], active [3], and dielectric

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resonators (DRs) [4]. On-chip lossy LC tanks are compact, hence offering a low-cost solution. However, their low Q at microwave frequencies translates to poor phase noise and high-power consumption. Quarter wavelength electromagnetic (EM) resonators have footprints on the order of 7.5 mm for a 10-GHz resonance, making them too bulky for handsets. DROs offer superior phase noise performance, but they are bulky and consume a large amount of power.

Alternatively, oscillators based on RF-MEMS resonators that harness the confinement of acoustic waves and have the size of hundreds of microns are attractive for portable devices. Recently, acoustic resonators with resonances above 10 GHz have been demonstrated in different platforms such as aluminum nitride (AlN) thin-film bulk acoustic resonators (FBARs) [5], AlN contour mode resonators (CMRs) [6], [7], scandium-doped AlN resonators [8], [9], ferroelectric resonators [10], FinFET resonators [11], and lithium niobate (LiNbO<sub>3</sub>) resonators [12]–[14]. From this group, LiNbO<sub>3</sub> resonators feature the highest demonstrated figure-of-merit (FoM<sub>RES</sub> =  $Q \times$  electromechanical coupling coefficient,  $k_t^2$ ) making them the more suitable candidate for enabling chip-scale oscillators with simultaneously low phase noise and low power consumption [15], [16].

To this end, this letter reports on the first acoustic microwave oscillator based on LiNbO<sub>3</sub> RF-MEMS resonators. A Ku-band Pierce oscillator using a third overtone LiNbO<sub>3</sub> resonator is presented. The oscillator is demonstrated with a phase noise of -70 and -111 dBc/Hz at 1 and 100-kHz offsets from a 12.9-GHz carrier, harnessing a third overtone characterized by a loaded quality factor ( $Q_t$ ) of 270,  $k_t^2$  of 1.9%, and an FOM<sub>RES</sub> of 5.1. The oscillator consumes a dc power of 20 mW achieving an FoM<sub>OSC</sub> of 200 dBc/Hz at 100-kHz offset. The demonstrated performance shows the strong potential of acoustic microwave oscillators to revolutionize the 5G frequency synthesis. Their main strength lies in offering small form factor and long battery life solutions with competitive phase noise results compared with other EM oscillators.

#### II. OSCILLATOR DESIGN

## A. Antisymmetric Mode LiNbO<sub>3</sub> RF-MEMS Resonators

Antisymmetric modes are a class of Lamb-wave modes characterized by their antisymmetric vibrations about the median plane of the plate. These modes have equal vertical but opposite longitudinal displacement components on the opposite sides of the median plane. The theory defining the resonant frequencies for the excited odd modes can be found in [12]. The higher order antisymmetric modes are confined in the unmetallized regions between any two electrodes. Such confinement is a result of the acoustic impedance mismatch between the metalized and unmetalized sections. Hence, half

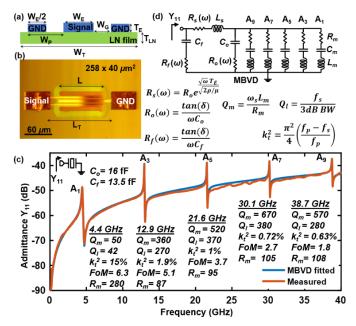


Fig. 1. (a) Mockup cross-sectional view of the LiNbO<sub>3</sub> resonator with key parameters is shown.  $W_T=21~\mu\text{m}, W_G=W_E/2=3~\mu\text{m}, T_E=50~\text{nm},$  the thickness of the electroplated Au pad is  $2~\mu\text{m}, T_{\text{LN}}=400~\text{nm}, L_T=142~\mu\text{m}, L=100~\mu\text{m},$  and the pad area is  $60~\times~40~\mu\text{m}^2$ . (b) Optical image of the fabricated resonator. (c) Measured and MBVD fit response for the first five odd modes. (d) Multiresonance equivalent MBVD model with parasitics included.  $\tan(\delta)$  is the loss tangent of LiNbO<sub>3</sub>,  $\rho$  is the resistivity of thin-film Au, and  $\mu$  is the permeability of Au. Mechanical  $(Q_m)$ , loaded  $(Q_I)$  quality factors,  $k_I^2$ , FoM, and  $R_m$  of each tone are shown.

the longitudinal wavelength ( $\lambda_l/2$ ) is approximately equal to the distance between the adjacent electrodes ( $W_G$ ). The resonance of an A-mode resonator is largely set by the thickness of the LiNbO<sub>3</sub> film ( $T_{\rm LN}$ ) and the mode order (m). Hence, for a resonator using a 400-nm-thick Z-cut LiNbO<sub>3</sub> film,  $\lambda_l=6~\mu{\rm m}$ , and m of 3, the  $A_3$  resonance rises beyond 10 GHz which is desired for investigating microwave acoustic oscillators.

The resonator comprised a three-electrode transducer on the top of a mechanically suspended Z-cut LiNbO3 thin film as shown in Fig. 1(a) and (b). The electrodes being connected to signal and ground induce lateral electric fields in the piezoelectric film, hence exciting the resonator into odd-order antisymmetric vibrations. The resonator was fabricated, with the dimensions given in the inset of Fig. 1, using a process described in [17]. A 50-nm gold (Au) is sputtered and lifted-off as top electrodes. Au probing pads of 60  $\times$  40  $\mu m^2$  are electroplated to 2- $\mu m$  thickness with a 200- $\mu m$  pitch to reduce the parasitics between the pads.

The resonator was measured and characterized using the Keysight N5230A PNA-L network analyzer. A thru-reflect-line (TRL) calibration is done in measurements using on-wafer standards. A multiresonance modified Butterworth-Van Dyke (MBVD) model shown in Fig. 1(d) is used to interpret the measured admittance shown in Fig. 1(c). The MBVD model includes an additional series inductor ( $L_s = 90$  pH) and a resistor ( $R_s = 13.4 \Omega$  at 13 GHz) to model the nonnegligible inductance and the surface resistance of the electrodes at high frequencies, respectively. It also includes a capacitor of 13.5 fF and a resistor ( $R_f$ ) to model the feedthrough capacitance ( $C_f$ ), and the resistive substrate loss, respectively. The resonator is also characterized by a static capacitance from the IDT ( $C_o$ )

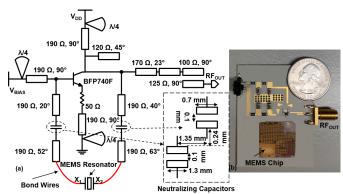


Fig. 2. (a) Simplified schematic of the RF portion of the 13-GHz oscillator. (b) Oscillator PCB.

of 16 fF, which is set by the size of the resonator. The loaded quality factor  $(Q_l)$  is measured for each resonance using the 3-dB bandwidth method, while the mechanical quality factor  $(Q_m)$  is extracted through the MBVD model by excluding the electrical loss.  $k_l^2$  is also extracted for each resonance considering all the device parasitics.

The first five odd modes,  $A_1$ ,  $A_3$ ,  $A_5$ ,  $A_7$ , and  $A_9$ , with resonances at 4.4, 13, 22, 30, and 39 GHz are characterized. The key measured and extracted parameters, including  $Q_l$ ,  $Q_m$ , and  $k_l^2$ , are shown in Fig. 1(c). For higher order modes,  $Q_l$  is 270 for  $A_3$  and 380 for  $A_7$ , while  $Q_m$  is 360 for  $A_3$ , and 670 for  $A_7$ . For these modes,  $Q_m$  varies from 1.3  $Q_l$  at 13 GHz to  $2Q_l$  at 39 GHz, indicating that mitigating electrical loss is crucial for high performance at microwave and mm-wave frequencies.  $k_l^2$  decreases from 15% for  $A_1$  to 0.63% for  $A_9$  with a value of 1.9% for  $A_3$ . The reason behind the degradation of  $k_l^2$  with an increasing mode order can be found in [12].

Optimizing the resonator for higher  $FoM_{RES}$  is desirable to enable oscillations with low-power consumption and good phase noise metrics. This can be achieved through improving the thin-film quality, using metals with lower mechanical losses for IDEs, and using SiC or sapphire as a substrate to reduce the dielectric loss.

## B. Pierce Oscillator

The Pierce oscillator shown in Fig. 2(a) is used to excite the resonator third overtone at 13 GHz. Infineon BFP740F silicon germanium (SiGe) n-p-n heterojunction bipolar transistor (HBT) is used for its low NF which is critical for low phase noise oscillations. The transistor has cut-off frequencies  $f_t$  of approximately 45 and 27 GHz at collector currents  $I_C$  of 25 and 5 mA. Rather than any higher order resonance,  $A_3$  is chosen for a low-power solution primarily due to the limitations of  $f_t$ . Bias voltages  $V_{CE}$  and  $V_{BE}$  of 2.7 and 0.8 V, respectively, are chosen for optimal phase noise performance while consuming 20 mW of dc power. A 50- $\Omega$  degeneration resistor is used to set the transistor bias and help in boosting the linearity at the expense of slightly higher power consumption.

The resonator-loading reactances needed for the Pierce operation at 13 GHz are realized mainly through the transistor junction capacitances ( $C_{\rm CB}$  of 80 fF,  $C_{\rm CE}$  of 0.3 pF, and  $C_{\rm BE}$  of 0.4 pF) and an open circuit stub of 120  $\Omega$  and 45° in electrical length at 13 GHz. The stub creates a reactance equivalent to a capacitance of 100 fF at the collector terminal. In addition, the resonator static capacitance  $C_o$ , the feedthrough

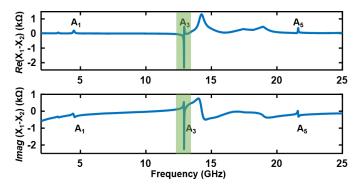


Fig. 3. Simulated real and imaginary input impedances across circuit nodes  $X_1$  and  $X_2$ . Only the third-order mode is excited.

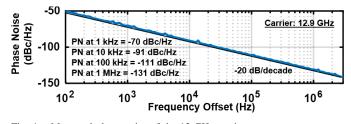


Fig. 4. Measured phase noise of the 13-GHz carrier.

capacitance  $C_f$ , and the printed circuit board (PCB) parasitic capacitances are also included in the loading reactance.

Bias-Tees are critical in the design for optimal performance. Open  $\lambda/4$  radial stub of low impedance is used to create an RF choke in the dc arm, hence allowing the dc bias and isolating RF from the bias network [not shown in Fig. 2(a)]. A high-impedance (190  $\Omega$ ) $\lambda/4$  line is used to transform the RF short to an RF open circuit at all the transistor terminals. Thus, the biasing arm does not load the RF path. The lengths of the quarter-wave stubs are chosen for 13 GHz. An output matching network is used for 50- $\Omega$  measurements. The network is designed to have a low insertion loss for high output power and low noise floor, while not loading the collector or worsen the flicker and thermal phase noises.

To satisfy the Barkhausen's loop-phase condition of oscillation, special attention is given to the trace between the base and the collector. Hence, the transmission lines' impedances, lengths, and the resonator wire bonds are extensively simulated using Keysight Momentum. Variations in the trace lengths will change the frequency of oscillation and the phase noise profile. Two capacitors in the positive feedback path are implemented as parallel traces to neutralize the wire bonds' inductances, and hence force the frequency of oscillation to be as close to  $A_3$  resonance as possible, thus enhancing the loaded Q and the phase noise. The oscillator is assembled on a Rogers RO3003 board with a thickness of 1.52 mm, a dielectric constant of 3, and a dissipation factor of 0.0013 at 10 GHz. The conditions of oscillation are satisfied for only the third-order resonance, while the fundamental and higher order resonances are suppressed as shown in Fig. 3.

# III. MEASUREMENTS

The active portion of the Pierce oscillator on the Rogers RO3003 board is integrated with the MEMS chip (2 cm×2 cm) through wire bonding. The assembly is shown in Fig. 2(b). Phase noise measurements are taken using an R&S FSUP26 signal analyzer and reported in Fig. 4. The oscillator

TABLE I COMPARISON TO THE SOA RF-MEMS OSCILLATORS ABOVE 5 GHz

		This work	[1	8]	[19]	[20]			
Resonator		LiNbO <sub>3</sub> 3 <sup>rd</sup> tone		AR nental	FBAR fundamen	FBAR tal 3 <sup>rd</sup> tone			
IC Process		discrete	$0.35 \mu m$	BiCMOS	discrete	discrete			
Osc. Freq. (GHz)		12.9	5.	46	5	7			
Resonator footprint (mm²)		0.01	0.034		> 0.1	-			
$Q_l$		270	300#		300	1350			
$k_t^2$ (%)		1.9	6.67#		4.3	-			
$FoM_{RES}$		5.1	20		12.9	-			
dc power (mW)		20	12.7		-	16.2			
PN (dBc/Hz)	1 kHz	-70	-64^	-56.5	-	-			
	100 kHz	-111	-117.7	-110.2	-109.5 -10	01 -80 -74.7			
	1 MHz	-131	-		-	-110-104.7			
FoM <sub>Osc</sub> (dBc/Hz)	100 kHz	200.2	201.4		-	164.8			

TABLE II

COMPARISON TO THE SOA EM OSCILLATORS

		This work	[4]			[2]	[3]	[1]
Resonator		LiNbO <sub>3</sub>	DRO			μstrip	Active	LC
IC Process		discrete	GaN	GaAs	SiGe	BJT	discrete	BiCMOS
Osc. Freq. (GHz)		12.9	10.6			10	10	15
Resonator footprint (mm²)		0.01	=			-	•	-
$Q_l$		270	600				1211	-
dc power (mW)		20	Ī			200	500	72
PN (dBc/Hz)	1 kHz	-70	-53 <sup>††</sup>	-76 <sup>tt</sup>	-90 <sup>ff</sup>	-65 <sup>†</sup>	-	-
	100 kHz	-111	-118 -116.3	-123 -121.3	-135 -133.3	-113 -110.8	-114.4 -112.2	-102* -103.3
FoM <sub>Osc</sub> (dBc/Hz)	100 kHz	200.2	-			190	187.4	187

The values in the shaded cells are referenced to a 12.9 GHz output. # as reported in [21]. ^ value estimated from a plot in [18]. †† value estimated from a plot in [4]. † value estimated from a plot in [1]. \*value estimated from a plot in [1].  $FoM_{OSC} = -L(\Delta f) + 20\log\left(\frac{f_o}{f_m}\right) - 10\log\left(\frac{P_{dc}}{1\,mW}\right), \text{ where } L(\Delta f) \text{ is the phase noise measured at an offset } f_m \text{ from a carrier } f_o, \text{ and } P_{dc} \text{ is the dc power consumption.}$ 

achieves a measured phase noise of -70 and -111 dBc/Hz at 1 and 100-kHz offsets from a 12.9-GHz carrier. The phase noise profile shows a -20 dB/decade trend between 100 Hz and 1 MHz offsets from the carrier. The -30 dB/decade trend is not captured in the region of interest due to the low flicker noise characteristics of the SiGe transistor. For the reported phase noise values, the oscillator consumes a dc power of 20 mW and achieves an FoM<sub>OSC</sub> of 200 dBc/Hz at 100-kHz offset. The measured output power is -8.5 dBm.

### IV. CONCLUSION

In comparison to the SoA in Tables I and II, the FoM of our oscillator surpasses those of the SoA EM and overtone MEMS oscillators. Moreover, the achieved oscillation frequency is the highest reported to date for an RF-MEMS oscillator. The demonstrated performance shows the strong potential of microwave acoustic oscillators for 5G frequency synthesis. They offer small form factors and long battery life solutions with competitive phase noise performance in comparison to other EM oscillators. Further reduction in footprint and power consumption can be achieved by realizing the active circuit with a recent CMOS node.

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